| L Number | Hits | Search Text | DB | Time stamp |
|---|---|---|---|---|
| 1 | 2 | 5941761.pn. | USPAT; EPO; JPO; DERWENT; IBM_TDB | 2004/10/01 08:05 |
| 2 | 46 | (CMP or "chemical mechanical polishing") and (pad same effector) and friction$3 | USPAT; EPO; JPO; DERWENT; IBM_TDB | 2004/10/01 08:23 |
| 3 | 35188 | CMP or "chemical mechanical polishing" | USPAT; EPO; JPO; DERWENT; IBM_TDB | 2004/10/01 09:02 |
| 4 | 104 | (CMP or "chemical mechanical polishing") and (pad same effector) | USPAT; EPO; JPO; DERWENT; IBM_TDB | 2004/10/01 09:02 |
| 5 | 133 | pad and effector and condition$4 and CMP | USPAT; EPO; JPO; DERWENT; IBM_TDB | 2004/10/01 09:03 |
| 6 | 1264 | pad and effector and condition$4 | USPAT; EPO; JPO; DERWENT; IBM_TDB | 2004/10/01 09:07 |
| 7 | 142 | (CMP or "chemical mechanical polishing" ) and (pad and effector and condition$4 ) | USPAT; EPO; JPO; DERWENT; IBM_TDB | 2004/10/01 09:04 |
| 8 | 2086 | ((438/691) or (438/692) or (438/693)).CCLS. | USPAT; EPO; JPO; DERWENT; IBM_TDB | 2004/10/01 09:05 |
| 9 | 17 | (((438/691) or (438/692) or (438/693)).CCLS.) and (pad and effector and condition$4 ) | USPAT; EPO; JPO; DERWENT; IBM_TDB | 2004/10/01 09:05 |
| 10 | 3097 | ((451/41) or (451/56) or (451/72)).CCLS. | USPAT; EPO; JPO; DERWENT; IBM_TDB | 2004/10/01 09:07 |
| 11 | 71 | (((451/41) or (451/56) or (451/72)).CCLS.) and (pad and effector and condition$4 ) | USPAT; EPO; JPO; DERWENT; IBM_TDB | 2004/10/01 09:07 |
| 12 | 1767 | (pad or cloth) and effector | USPAT; EPO; JPO; DERWENT; IBM_TDB | 2004/10/01 09:07 |
| 13 | 73 | (((451/41) or (451/56) or (451/72)).CCLS.) and ((pad or cloth) and effector  ) | USPAT; EPO; JPO; DERWENT; IBM_TDB | 2004/10/01 09:07 |